ALBUQUERQUE • AMHURST • AUSTIN • COLORADO SPRINGS • CORBEIL-ESSONNES • DALLAS • DRESDEN • FREMONT • HSIN-CHU • ICHEON • MAINHARDT

MESA • MONZA • NIJMEGAN • OCEANSIDE • ROUSSET • SAN JOSE • SEOUL • SHANGHAI • SINGAPORE • TOKYO • VANCOUVER • WILSONVILLE

thermoelectric point-of-use (POU) chillers

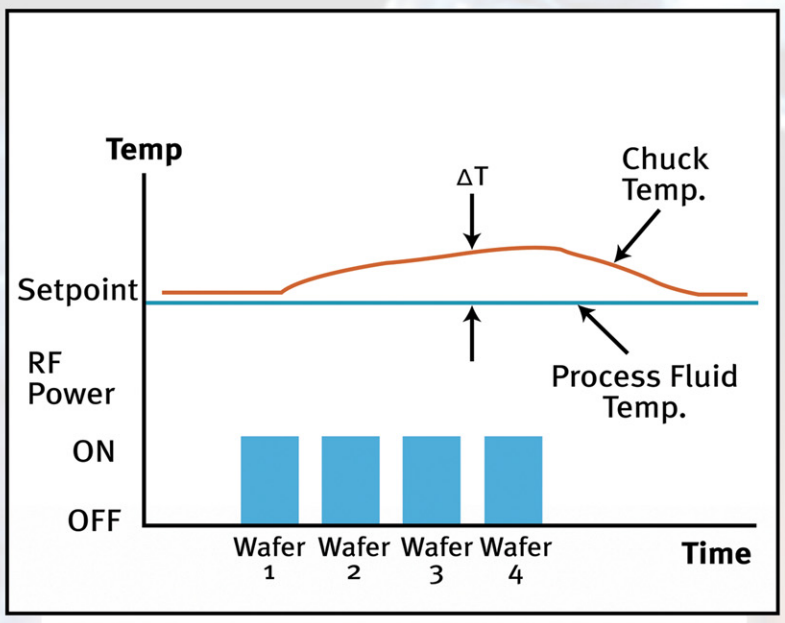
REDUCED OPERATING COST — 50% less power consumed — BY DESIGN

Experience the POU evolution

dynamic temperature control * smallest footprint in the industry enables POU installations lowest power consumption * sub-floor tile mount capability * zero temperature drift reliable solid-state operation & only one moving part * multi-platform interfacing capability only 1 gallon of coolant required * synchronized with the process

process improvement & comparison

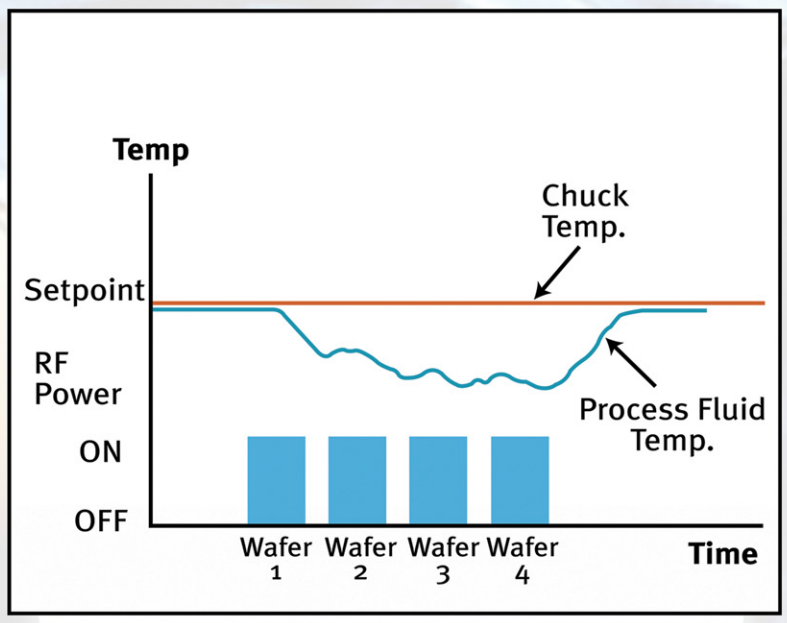
conventional



temperature drift

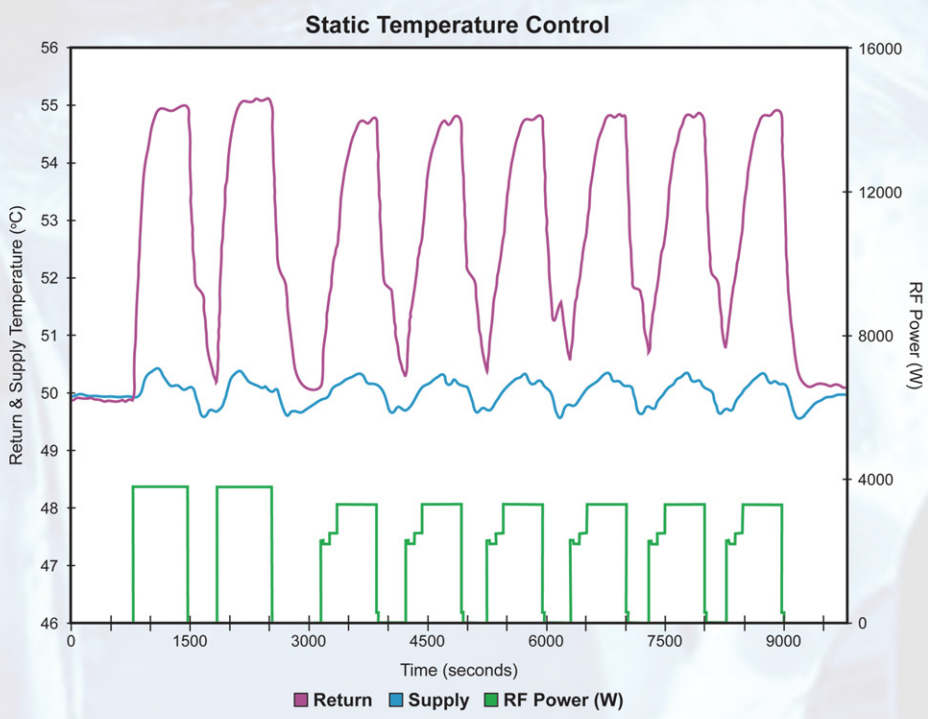
- negative effect on side wall passivation
- wafer-to-wafer temperature instability
- reservoir fluid temperature constant
- chuck temperature varies
- unstable etch rates

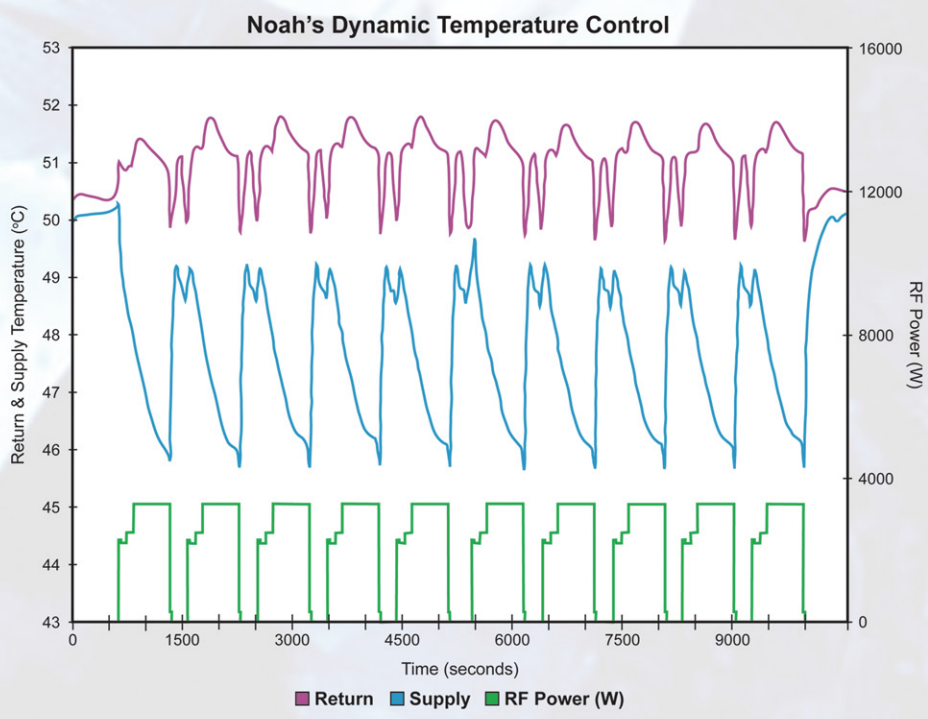
POU



improved control

- fluid supplied temperature varies
- chuck temperature constant
- reduced 'First Wafer Effect'
- wafer-to-wafer stability
- improved CD bias
- stable etch profile





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